Record of Letter Ballot Review by TC Chapter for Procedural Review

Region/Locale: Japan Global Technical Committee: Silicon Wafer TC Chapter Cochairs: Tetsuya Nakai (SUMCO), Naoyuki Kawai (Meiji University) Ryuji Takeda (GWJ) Standards Staff: Mami Nakajo

	Scheduled in Background Statement	Actual		
Date	7/21/2020	01/15/2021		
Location	San Francisco, CA	Tokyo, Japan		
Reason for Change of Date and/or Location (if changed)	COVID-19 pandemic			

Note: See Regulations ¶ 9.5 Exceptions for allowable reason to change.

I. Document Number and Title

Document Number 6363	Document Title Revision of SEMI M52-0214 With Title Change To: Guide For Specifying Scanning Surface Inspection
	Systems For Silicon Wafers For The 130 nm To 5 nm Technology Generations

II. Tally

Standards staff to fill in.

Voting Tally: As-cast tally after close of voting period

Note: A minimum of 60% of the Voting Interests that have TC Members within the global technical committee that issued the Letter Ballot must return Votes. (*Regulations* ¶ 9.6.2.1.1)

Voting Tally:

Voting Interest:	Returned Votes		Distribution		Return Rate	
Letter Ballot	55		91	=	60.4%	≥60%
Intercommittee Ballot	31]				
Voting Interest Reject(s)	0]	Total	Vote	rs with Rejects	0
Voting Interest Accept(s)	42					

Note: See *Regulations* § 3.2.1 for definition of Voting Interest.

III. Rejects

None

IV. Other Technical Issues

V. Comments

V- (i) Voters' Comments Commenter 1 (David Hyde/SCREEN) - Comment 1

Com	*TF/TC Chapter to fill in section/paragraph #, if necessary.								
Comment		In general no issues seen, however I am unable to comment on contents of Table 3, therefore I will abstain. Thank you for all of your hard work.							
	The	e TC Chapt	ter aç	greed to do one of the following actions.					
	*No	*No motion is required in this step.							
A		Already ad	Already addressed by Commenter #, Comment #						
Action	х	No further	actio	tion was taken by the TC Chapter.					
٢		Refer to th	fer to the TF for more consideration.						
		New Business							
		Editorial C	Chang	je					
		Options		Case 1: No vote in this section:					
		for editorial		To be included and voted on as a group in § VI. Editorial Changes Other than Those Voted on in § V.					
		change		Case 2: Voted in this section:					
		(check one)		Original section number and at least one full sentence are required in "FROM" and "TO" fields.					

This table is needed for each Comment accompanied a Vote

Commenter 2 (Richard Allen/NIST) - Comment 1

		Chapter to fill in section/paragraph #, if necessary. Wording in Scope
Comment		 Section 2.1: Please change the beginning of the second sentence for clarity. My suggestion would be to change as follows: Current: Recommendations for the 130-11 nm generations are unchanged from previous versions of this Guide. The 7 and 5 nm node characteristics Replacement: Recommendations for the 130 nm – 11 nm generations are unchanged from previous versions of this Guide. The 7 nm and 5 nm node characteristics
	The T	C Chapter agreed to do one of the following actions.

Γ	*No	No motion is required in this step.						
		Already addressed by Commenter #, Comment #						
		No further	acti	on was taken by the TC Chapter.				
		Refer to the TF for more consideration.						
		New Business						
	x Editorial Change							
		Options	ne.	Case 1: No vote in this section:				
		for editorial change	х	To be included and voted on as a group in § VI. Editorial Changes Other than Those Voted on in § V.				
				Case 2: Voted in this section:				
		(check one)		Original section number and at least one full sentence are required in "FROM" and "TO" fields.				

This table is needed for each Comment accompanied a Vote

Commenter 2 (Richard Allen/NIST) - Comment 2

	*TF/TC Chapter to fill in section/paragraph #, if necessary.							
	2. Issues with LSE (multiple locations)							
Comment	 a. Please make clear what LSE means on first use. The COT has two definitions, "latex sphere equivalent" and "light scattering equivalent", either of which could apply based on context. 							
		b.	Tab	ble 1, line 1.13: need space between "nm" and "LSE" (4X)				
		C.	Tab	ble 3, line 3.1: need space between "nm" and "LSE" (4X)				
	The	e TC Chapt	ter ag	greed to do one of the following actions.				
	*No motion is required in this step.							
A		Already addressed by Commenter #, Comment #						
Action		No further action was taken by the TC Chapter.						
ſ		Refer to the TF for more consideration.						
		New Busi	ness					
	x Editorial Change							
		Options		Case 1: No vote in this section:				
		for editorial	х	To be included and voted on as a group in § VI. Editorial Changes Other than Those Voted on in § V.				
		change		Case 2: Voted in this section:				
		(check one)		Original section number and at least one full sentence are required in "FROM" and "TO" fields.				

Commenter 3 (Frank Riedel/Siltronic) - Comment 1

*TF/TC Chapter to fill in section/paragraph #, if necessary.

Comm	1) Section 5.3.12 states "For sizing calibration, deposition CRMs are available from a variety of sources." Unfortunately, for haze CRMs are not available. SEMI M52 does not mention at all neither haze "calibration" nor haze matching. I consider desirable having this topic included.							
	The	e TC Chapt	er ag	greed to do one of the following actions.				
	*No	motion is	requ	ired in this step.				
A		Already ad	Already addressed by Commenter #, Comment #					
Action		No further	No further action was taken by the TC Chapter.					
٢		Refer to th	Refer to the TF for more consideration.					
	х	New Busir	New Business					
		Editorial Change						
		Options for editorial change (check one)		Case 1: No vote in this section:				
				for		To be included and voted on as a group in § VI. <i>Editorial Changes Other than Those Voted on in § V.</i>		
				Case 2: Voted in this section:				
				Original section number and at least one full sentence are required in "FROM" and "TO" fields.				

Commenter 3 (Frank Riedel/Siltronic) - Comment 2

Com	*TF/TC Chapter to fill in section/paragraph #, if necessary.								
Comment	lim	Table 3 Item 5.3 Calibration states "The number of calibration points <120 nm islimited to 4." This is true for KLA SP1. Is this statement still valid for later LLSequipment generations?							
	The	e TC Chapt	ter ag	greed to do one of the following actions.					
	*Nc	*No motion is required in this step.							
Δ		Already addressed by Commenter #, Comment #							
Action		No further action was taken by the TC Chapter.							
р		Refer to the TF for more consideration.							
		New Business							
	х	Editorial Change							
		Options		Case 1: No vote in this section:					
		for editorial	х	To be included and voted on as a group in § VI. Editorial Changes Other than Those Voted on in § V.					
		change (check		Case 2: Voted in this section:					
		one)		Original section number and at least one full sentence are required in "FROM" and "TO" fields.					

Commenter 3 (Frank Riedel/Siltronic) - Comment 3

*TF/TC Chapter to fill in section/paragraph #, if necessary.

C.	Table 3 Item 5.3 Calibration refers to SEMI M53 with respect to details of calibration procedure. Is the reference still valid for latest SP7 technology?															
	The	e TC Chapt	er aç	greed to do one of the following actions.												
	*Nc	motion is	requ	ired in this step.												
A		Already addressed by Commenter #, Comment #														
Action	х	No further	Io further action was taken by the TC Chapter.													
٢		Refer to th	r to the TF for more consideration.													
		New Business														
		Editorial Change														
	Options			Case 1: No vote in this section:												
		for editorial		for	for	for	for	for	for	for	for	for	for	for		To be included and voted on as a group in § VI. Editorial Changes Other than Those Voted on in § V.
		change (check		Case 2: Voted in this section:												
		one)		Original section number and at least one full sentence are required in "FROM" and "TO" fields.												

Commenter 3 (Frank Riedel/Siltronic) - Comment 4

Comment	*TF/TC Chapter to fill in section/paragraph #, if necessary.								
nent		Here is a request for Table 3 "Metrology Specific Equipment Characteristics": Replace PSL by PSL/Silica, this way indicating both types of spheres are addressed.							
	The	e TC Chapt	ter aç	greed to do one of the following actions.					
	*No	motion is	requ	ired in this step.					
Þ		Already ad	dy addressed by Commenter #, Comment #						
Action	х	No further	further action was taken by the TC Chapter.						
ſ		Refer to th	fer to the TF for more consideration.						
		New Business							
		Editorial Change							
		Options		Case 1: No vote in this section:					
		for editorial		To be included and voted on as a group in § VI. <i>Editorial Changes Other than Those Voted on in § V.</i>					
		change		Case 2: Voted in this section:					
	(check one)			Original section number and at least one full sentence are required in "FROM" and "TO" fields.					

V-(ii) Comments Created by Handling Negative

None

VI. Editorial Changes Other than Those Voted on in § V

Original section/paragraph number and at least one full sentence are required in "FROM" and "TO" fields.

		x								
	Origin of this editorial change		Commenter 2/ Comment 1							
	(Check one)		Other []							
	FROM:									
1	2.1 This Guide outlines and recommends basic specifications for SSIS equipment used for the 130, 90, 65, 45, 32, 22, 16, 11, 7, and 5 nm technology generations. Recommendations for the 130-11 nm generations are unchanged from previous versions of this Guide. The 7 and 5 nm node characteristics are taken from the 2018 edition of the International Roadmap for Devices and Systems (IRDS) ¹ , the successor to the International Technology Roadmap for Semiconductors (ITRS).									
	TO:									
	2.1 This Guide outlines and recommends basic specifications for SSIS equipment used for the 130, 90, 65, 45, 32, 22, 16, 11, 7, and 5 nm technology generations. Recommendations for the 130 nm - 11 nm generations are unchanged from previous versions of this Guide. The 7 nm and 5 nm node characteristics are taken from the 2018 edition of the International Roadmap for Devices and Systems (IRDS) ¹ , the successor to the International Technology Roadmap for Semiconductors (ITRS).									
	Justification: (If necessary) Editorial, clarifying the unit.									
	Origin of this editorial change	x	Commenter 2/ Comment 2							
	(Check one)		Other []							
	FROM: 5.4.3 All size units of LLS are given in [length unit]LSE (e.g., nmLSE) and refer to a nominal									
	diameter.									
2	TO:									
	5.4.3 All size units of LLS are given in [length unit]LSE (e.g., nmLSE) and refer to a nominal diameter.									
	NOTE XX: In this document, the initialism <i>LSE</i> has the specific meaning <i>latex sphere equivalent</i> , rather than the general term <i>light scattering equivalent</i> . <i>Latex</i> refers to polystyrene spheres, polymerized in water suspension (hence <i>latex</i>) from the styrene monomer, to produce nearly perfect, highly monodisperse spherical nanoparticles. Although the most advanced SSIS systems use other materials (chiefly silica) for calibration and matching, widespread industry practice reports SSIS sizes and sensitivity thresholds in terms of [length unit]LSE. JUstification: Editorial. Add a NOTE to explain that intended meaning is "latex sphere equivalent".									

			1					
	Drigin of this editorial change (Check one)		Commenter 3/	Comment 2				
(Cł	neck one)		Other []					
FROM: Tab Row 5.3	le 3 Metrology Sp	ecifi	c Equipment C	haracteristics				
5.3 Calibration	points <120 nr inte between calibratio using the calcula	n is linerpolation poir ted an	per of calibration mited to 4. The tion nts will be done by d system specific ve (SEMI M53).	In order to reduce PSL or silica sphere sizing uncertainty in the 65–200 nm range, the diameter distribution should have a full width at half maximum (FWHM) \leq 5%. In addition, it is desirable that the peak PSL diameter as deposited on the wafer have a relative expanded uncertainty at about 95% confidence level as small as possible but not greater than 3% (see SEMI M53, SEMI M58)				
TO: FROM: Row 5.3	Table 3 Metrolog	y Spo	ecific Equipme	nt Characteristics				
5.3 Calibration	points <120 nm inte between calibration using the calcula	n is lin erpolat on poir ted an		In order to reduce PSL or silica sphere sizing uncertainty in the 65–200 nm range, the diameter distribution should have a full width at half maximum (FWHM) \leq 5%. In addition, it is desirable that the peak PSL diameter as deposited on the wafer have a relative expanded uncertainty at about 95% confidence level as small as possible but not greater than 3% (see SEMI M53, SEMI M58)				
#6 Many advanc over time.	ced SSIS tools have addition	onal ca	libration points < 120	nmLSE as their minimum detectable particle sizes have improved				
	ete (editorial chang rate with advance	ge): More than 4 calibration points exist for more advanced S ed sensitivity. Seller and buyer may mutually to any numbe						
	o approve the abo	ve ec	litorial change(s).				
otion by/ 2 nd by	Kurt Haller (<mark>KLA</mark>)/ K	Kenji Oka (Hitachi High-Tech)						
scussion N	None							

VII. Approval Conditions Check

VII. - (i). Approval Rate

APPROVAL CONDITION 1: All Negatives have been discussed and were withdrawn, found not related, found not persuasive, or addressed by a technical change. (*Regulations* ¶ 9.6.2.1.2)

APPROVAL CONDITION 2: At least 90% of the sum of valid Voting Interest Accept and Voting Interest Reject Votes must be Accept. (*Regulations* ¶ 9.6.2.1.3)

		Accepts		(Accepts + Valid Rejects)			
Approval Rate	=	42	/	42	=	100.0%	≥90%

Note: If both approval conditions are not satisfied, the Document fails.

VII. – (ii) Approval Level (check one)

Note: See Regulations § 9.6.2 for further information.

Globally Approved (No Ratification Ballot needed): The Letter Ballot meets the Letter Ballot approval conditions for the global technical committee.

Need a Ratification Ballot:

The Letter Ballot meets the Letter Ballot approval conditions for the TC Chapter and a Ratification Ballot will be issued to validate technical changes.

VIII. Safety Check

X

Note: See Regulations § 15 for further information.

	x	This is not a Safety Document, when all safety-related information is removed, the Document is still technically sound and complete. (<i>Regulations</i> \P 8.7.1)										
Motion				y Document , when all safety-related information is removed, the Document is not nd and complete. (<i>Regulations</i> \P 8.7.2)								
ſ				ecklist (<i>Regulations</i> ¶ 15.3) is complete and has been included with the Document the balloting process. (<i>Regulations</i> ¶ 15.1.2)								
	Moti	ion b	oy/2 nd by	Kurt Haller (KLA)/ Kenji Oka (Hitachi High-Tech)								
	None											
Vote 8 Y-0 N; Motion passed												

IX. Intellectual Property (IP) Check

Note: This Letter Ballot may cover all or part of a Standard or Safety Guideline. Regardless of the coverage, this IP check applies to the entire Standard or Safety Guideline*. See *Regulations* § 16 for further information.

X The TC Chapter meeting chair asked those participating, if they were aware of any patented technology that might be relevant (see *Regulations* ¶ 16.3.1.1) to the Standard or Safety Guideline; or, any copyrighted items or trademarks that are used/reproduced (see *Regulations* ¶ 16.4.1.2) in the Standard or Safety Guideline. (Also see, *Regulations* § 8.8)

Х	The question is NOT answered in affirmative (No potentially material patented technology or use/reproduction of copyrighted items/trademarks is known.)	GO TO SECTIO	NC	Х.	
	The question is answered in affirmative	Is any of the known IPs a patented		Yes, at least one of them is a patented technology	GO TO IX (a) "Patented Technology" subsection
		technology?		No	GO TO IX (b) "Copyright items" subsection

IX(a) Patented Technologies subsection IX(a1) Total numbers of Patented Technologies to be dealt with

# Fill	(I) Known Patented Technology that might be relevant to	# Fill	technologies first became known to the TC Chapter on or after the day	Postpone assessment of such patented technologies to be performed at the next scheduled TC Chapter meeting.
numbe	r the Standard/Safety Guideline	" Fill	(n) Number of patented technologies first became known to the TC Chapter before the day of the issuance of this Letter Ballot	GO TO IX (a2)

IX(a2) Assessment of disclosed patented technologies

Disclosed patented technology #1 (Brief description, e.g., patent title and number):				Date of Assessment (If different from the date of Letter Ballot adjudication) MM/DD/YYYY				
Is disclosed patented	Pi			e of this echnically		YES	PROCEED to assess NEXT one, or if this is the last one, GO TO IX(a3)	
technology #1 found to be "might be material" to the Standard/Safety Guideline?			justified	ed?		NO	The Document is failed and returned to the TF	
		NO	No furth	er action is needed for patented technology #1				

This table is needed for each disclosed patented technology.

IX(a3) LOA status check of PMPT of which inclusion assessed to be justified

LOA Status of PMPT #1	LOA Status of PMPT #1										
Has an LOA for this		YES		PROCEED to check NEXT one, or if this is the last one, GO TO IX(b)							
patented technology been received from		NO	M		Ask ISC for spe	ecial permission to publish.					
every owner ?			ΟΤΙΟ		Quit activity.	The Document is failed and returned to the TF					

		Wait for LOA	PROCEED to check NEXT one, or if this is the last one, GO TO IX(b1)			
Motion by/ 2 nd by			Name (Company)/Name (Company)			
Dis	cuss	ion	XXXX			
Vote			XX Y-XX N; Motion passed (or failed)			

This table is needed for each PMPT of which inclusion assessed to be justified.

IX(b1) Total numbers of copyrighted items to be dealt with

	(o) Known copyrighted items that are used or reproduced to the	 o > 0 There is at least one known copy righted items that might be relevant to the Standard/Safety Guideline 	GO TO IX (b2)
number	Standard/Safety Guideline	o = 0 There is no disclosed copyrighted item	GO TO IX (c)

IX(b2) Assessment of disclosed copyrighted items

Disclosed copyrighted item #1 (Brief description of its use in the Document):									
Is disclosed copyrighted		YES	Is the use/reproduction of		YES	PROCEED to assess NEXT one, or if this is the last one, GO TO IX(b3)			
item #1 used or reproduced in the Standard/Safety Guideline?			this copyrighted item technically justified?		NO	The Document is failed and returned to the TF			
		NO	No further action is nee	ded f	or copyrig	hted item #1			

This table is needed for each disclosed copyrighted item.

IX(b3) Copyright release status check of copyrighted item of which inclusion assessed to be justified

Copyright release Statu	Copyright release Status of copyrighted item #1										
		YES		PROCEED to assess NEXT one, or if this is the last one, GO TO IX(c)							
Has the copyright		NO	MC		Ask ISC for special p	ermission to publish.					
release been received from its owner ?.			MOTION		Quit activity.	The Document is failed and returned to the TF					
					Wait for copyright release letter	PROCEED to check NEXT one, or if this is the last one, GO TO IX(c)					
			Mot	tion	by/ 2 nd by	Name (Company)/Name (Company)					
			Discussion			XXXX					
Vote						XX Y-XX N; Motion passed (or failed)					

This table is needed for each copyrighted item of which use/reproduction assessed to be justified.

	dominiou)	adoman		
		la overvinetence of	YES	GO TO IX(d)
Is there any trademark in the Standard/Safety Guideline?	YES	Is every instance of trademark use technically justified?	NO	The Document is failed and returned to the TF
	NO	GO TO IX(d)	-	

IX(c) Assessment of disclosed (identified) trademark

IX(d) IP check completion condition check

The co-chair checks if any Patented Technologies first become known to the TC Chapter on or after the day of the issuance of this Letter Ballot? i.e., m>0 in IX(a1)	YES	Sections IX(a2) and IX(a3) shall be completed and recorded for such patented technologies at next scheduled meeting of the TC Chapter. Until then, the TC Chapter shall NOT go to X (making motion to pass/fail this Document) (see <i>Regulations</i> ¶ 16.4.1.2) Until then this Letter Ballot Review is on hold.
	NO	GO TO X

X. Action for This Document

			ocument passed TC Chapter review as balloted and will be forwarded to the ISC A&R procedural review.				
Motion	x		ocument passed TC Chapter review with editorial changes and will be forwarded to the &R SC for procedural review.				
		editorial ch	becument passed TC Chapter review with technical changes and with or without I changes and will be forwarded to the ISC A&R SC for procedural review. A ation Ballot will be issued to verify the technical changes.				
		This Docu	ment failed TC Chapter review and will be returned to the TF for rework.				
		This Document failed TC Chapter review and work will be discontinued.					
Motion by/ 2 nd byKurt Haller (KLA)/ Kenji Oka (Hitachi High-Tech)			Kurt Haller (<mark>KLA</mark>)/ Kenji Oka (Hitachi High-Tech)				
Discussion None		None					
Vote 8 Y-0 N			8 Y-0 N				
Final Action		Action	X Motion passed				
			Motion failed				

Note: If the use of PMPT or copyrighted item is justified by the TC Chapter, LOA or release form must be received before publication can proceed.